

### Feature

- Precision MEMS process
- High performance, shielded, Micro-cavity structure
- Silicon substrate, 50Ω CPW output
- Au wire bonding, for MCM applications

### Environmental Specifications

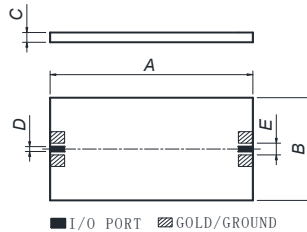
Operating Temperature	-55°C~+85°C
Storage Temperature	-55°C~+125°C
Max. Input Power	35dBm

### Electrical Specifications(T<sub>A</sub>=+25°C)

Parameter	Min.	Typ.	Max.	Unit
Center Freq. (f <sub>0</sub> )	-	11.57	-	GHz
Pass Band	11.35	-	11.8	GHz
Ripple in Pass band	-	-	1	dB
Insertion Loss @ f <sub>0</sub>	-	-	4.5	dB
Return Loss	15	-	-	dB
Out of band	≥30@10.9GHz&12.3GHz			dB
Attenuation	≥40@10.7GHz&12.35GHz			dB
Group Delay Variation	≤0.5@11.35~11.8GHz			ns
Linear Phase	≤±3@11.35~11.8GHz			°

S2P file name: SiMS11R7\_R12-8D3.s2p

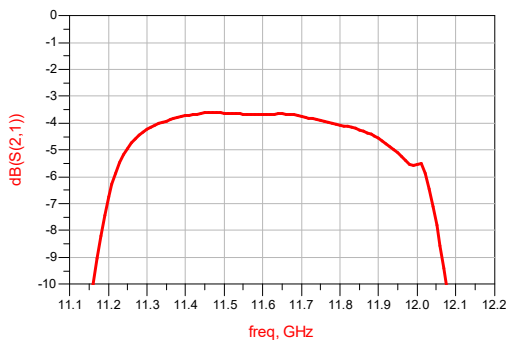
### Outline Drawing



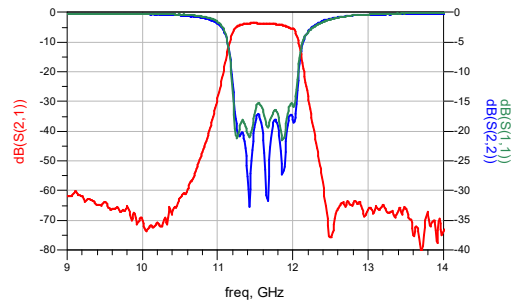
Symbol	Value (mm)		
	Min.	Nominal	Max.
A	10.9	-	11.0
B	4.4	-	4.5

### Typical Test Curves

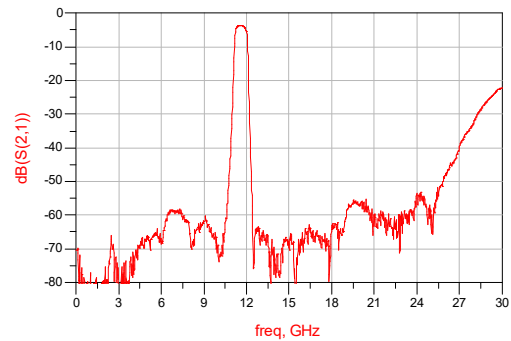
Insertion Loss VS Frequency (T<sub>A</sub>=25°C)



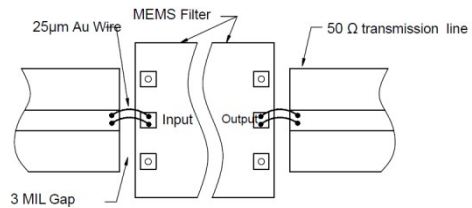
Insertion Loss & Return Loss VS Frequency (T<sub>A</sub>=25°C)



Broadband Insertion Loss VS Frequency (T<sub>A</sub>=25°C)

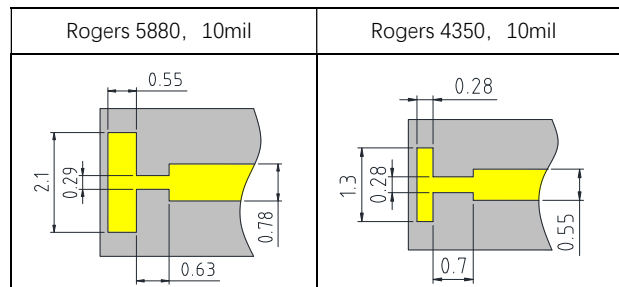


### Recommended Assembly Diagrams



### Application Notes:

1. The chip is back-metalized and can be die mounted with AuSn eutectic performs or with electrically conductive epoxy (for example ME8456).
2. The die should be assembled on carriers like Kovar or Mu-Cu which have same Coefficient of thermal expansion. (2.9ppm/°C) with Silicon, thickness 0.2mm max.
3. Handle the chips in a clean environment. DO NOT attempt to clean the chip using liquid cleaning systems.
4. Handle the chip along the edges with a vacuum collet or with a sharp pair of bent tweezers.
5. Recommended to use T structure as below for bonding.



6. If you have any questions, please contact us.